

trode 138 located on each of the protrudent portions 134 is contacted with the conductive pad 158 of the net-shaped metallic lines 125. Referring to FIG. 7, the touch position divides the lengthwise metallic lines into the first and second resistance lines (the first resistance line has the first resistance R_1 , and the second resistance line has the second resistance R_2), and divides the widthwise metallic lines into the third and fourth resistance lines (the third resistance line has the first resistance R_3 , and the fourth resistance line has the fourth resistance R_4). The voltages of divided resistance lines are proportional to resistance, and are shown in the following equations:

$$V_x = V \times R_3 / (R_3 + R_4)$$

$$V_y = V \times R_1 / (R_1 + R_2)$$

Wherein V_x is the voltage of the third widthwise resistance line, V_y is the voltage of the first lengthwise resistance line, and V is rated voltage (e.g. 5 volts). If the diameters of the resistance lines are the same, the voltages of divided resistance lines are proportional to the lengths of divided resistance lines, thereby calculating a coordinate of the touch position.

[0032] The relative circuit of the touch-sensitive functions is designed in the touch-sensitive LCD panel of the present invention. When the touch-sensitive LCD panel is manufactured, the circuit of the touch-sensitive function can be finished simultaneously. The touch-sensitive LCD panel of the present invention has no optical loss, but has touch-sensitive function. Furthermore, it is not necessary to extra add a conductive layer and a flat insulating layer so as not to increase manufacture cost and time. In addition, the spacers and the protrudent portions can be made by the same material and by the same manufacture processes so as not to also increase manufacture time.

[0033] Referring to FIG. 8, according to the TFT substrate 112 in this embodiment, the electrode layer 124 can include a plurality of scan lines 162 and data lines 164, which are disposed above the transparent substrate 120. The scan and data lines 162, 164 cross each other, thereby defining a plurality of pixel regions 160. The widthwise metallic lines 152 are parallel to the scan lines 162, and the lengthwise metallic lines 154 are parallel to the data lines 164. The widthwise metallic lines 152 and the scan lines 162 are located the same level, and the lengthwise metallic lines 154 and the data lines 164 are located the same level. Those skilled in the art understand that a second insulating layer (not show) is disposed between the scan lines 162 and the data lines 164. Thus, the second insulating layer is also disposed between the widthwise metallic lines 152 and the lengthwise metallic lines 154. The conductive pads 158 are electrically connected to the net-shaped metallic lines 125 by forming a plurality of plated through holes (PTHs) 172, 174 in the first and second insulating layers and forming a plurality of metallic extension layers 176 on the first insulating layer. For example, each conductive pad 158 is electrically connected to the widthwise metallic line 152 by the metallic extension layer 176 and the PTH 172, and is electrically connected to the lengthwise metallic line 154 by the metallic extension layer 176 and the PTH 174. The metallic extension layers 176 can be made of transparent metal. Or, referring to FIG. 9, in an alternate embodiment, each conductive pad 158 is directly electrically connected to the widthwise metallic line 152 and the lengthwise metallic line 154. In addition, the arrangement density of the widthwise metallic line 152 and the lengthwise metallic

line 154 depends on the requirement, e.g. one widthwise metallic line 152 and one lengthwise metallic line 154 per one, four or nine pixels 160 are arranged.

[0034] Referring to FIG. 10, according to the TFT substrate 112 in another embodiment, the electrode layer 124 can also include a plurality of scan lines 162 and data lines 164, which are disposed above the transparent substrate 120. The widthwise metallic lines 152 and the lengthwise metallic lines 154 are located above the scan lines 162. Those skilled in the art understand that a third insulating layer (not show) is disposed between the scan lines 162 and the data lines 164. The conductive pads 158 are electrically connected to the net-shaped metallic lines 125 by forming a plurality of plated through holes (PTHs) 182 in the third insulating layer. For example, each conductive pad 158 is directly electrically connected to a connection between the widthwise metallic line 152 and the lengthwise metallic line 154 by the single PTH 182.

[0035] Referring to FIG. 11, according to the TFT substrate 112 in a further embodiment, the electrode layer 124 can include a plurality of pixel electrodes 166, which are disposed above the transparent substrate 120. Referring to FIG. 12, the widthwise metallic lines 152 and the lengthwise metallic lines 154 are located on the same level, and are exposed from the first insulating layer. Thus, the conductive pads 158 can be directly electrically connected to the net-shaped metallic lines 125 without any PTH. For example, each conductive pad 158 is directly disposed at a connection between the widthwise metallic line 152 and the lengthwise metallic line 154.

[0036] Referring to FIG. 13, it depicts a method for calculating a coordinate of a touch position of a touch-sensitive LCD panel according to an embodiment of the present invention. In step 200, a TFT substrate is provided, wherein the TFT substrate includes a net-shaped metallic lines and a plurality of conductive pads, and conductive pads are arranged in array manner. The net-shaped metallic lines include a plurality of widthwise metallic lines, lengthwise metallic lines and connections constituted by crosses of the widthwise metallic lines and the lengthwise metallic lines. The conductive pads are electrically connected to the net-shaped metallic lines. In step 202, a CF substrate is provided, and is opposite to the TFT substrate. The CF substrate includes a plurality of spacers, a plurality of protrudent portions and a transparent electrode, wherein the spacers are adapted to keep the first predetermined gap between the TFT substrate and the CF substrate, there is the second predetermined gap between each protrudent portion and the corresponding conductive pad, and the transparent electrode covers the spacers and the protrudent portions. In step 204, the transparent electrode located on the protrudent portion is electrically contacted with the corresponding conductive pad according to a touch position, wherein the touch position divides the widthwise metallic lines to the first and second widthwise resistance lines, and divides the lengthwise metallic lines into the first and second lengthwise resistance lines. In step 206, a coordinate of the touch position is calculated by voltages of the divided resistance lines (e.g. the first and second widthwise resistance lines and the first and second lengthwise resistance lines) of the net-shaped metallic lines being proportional to lengths of the divided resistance lines.

[0037] Referring to FIG. 14, it depicts a method for manufacturing a TFT substrate according to an embodiment of the present invention. In step 300, a transparent substrate is provided. In step 302, net-shaped metallic lines are formed on the transparent substrate, wherein the net-shaped metallic lines